

ABSTRACT OF THE DISCLOSURE

5 The invention regards to a microlithography projection objective for short wavelengths, preferably ≤ 193 nm, with an entrance pupil and an exit pupil for the imaging of an object field in an image field, which represents a segment of a ring field, wherein the segment has an axis of symmetry and an extension perpendicular to the axis of symmetry, and the extension is at least 20, and preferably 25 mm.

10 The microlithography projection objective comprises
-- a first (S1), a second (S2), a third (S3), a fourth (S4), a fifth (S5), and a sixth mirror (S6) in centered arrangement relative to an optical axis, whereby
--each of these mirrors has a off-axis segment, in which light beams
15 impinge, which have been guided through the projection objective.

whereby

20 as a function of the numerical aperture NA of the exit pupil, the diameter of the off-axis segment of the first, second, third, fourth, fifth and sixth mirrors is ≤ 1200 mm * NA.